Special Issue

Processes in Electrical, Electronics and Information Engineering

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This Special Issue on “Processes in Electrical, Electronics and Information Engineering” seeks high-quality works focusing on the latest novel advances in membrane technology for both gas and liquid separation. Topics include but are not limited to:

- Electrical and electronics engineering
- Communications and computer systems
- Automation and control engineering
- Informatics and computer sciences
- Information engineering

Guest Editor

Prof. Dr. Wen-Jer Chang
Department of Marine Engineering, National Taiwan Ocean University, Keelung 202, Taiwan

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Processes
Editorial Office
MDPI, Grosspeteranlage 5
4052 Basel, Switzerland
Tel: +41 61 683 77 34
processes@mdpi.com

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Editor-in-Chief

Prof. Dr. Giancarlo Cravotto
Department of Drug Science and Technology, University of Turin, Via P. Giuria 9, 10125 Turin, Italy

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